#9/ A 16/03

## IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Application of:

Denis et al.

Serial No.

09/836,884 April 17, 2001

Filed: For:

PROCESS FOR FABRICATING THIN FILM

**TRANSISTORS** 

**Art Unit:** 

2823

Examiner:

Nguyen, K.D.

Cambridge, Massachusetts April 28, 2003

## **AMENDMENT**

Assistant Commissioner for Patents Washington DC 20231

Via facsimile to 703-746-9179

Sir:

In response to the Office Action issued October 28, 2002 in connection with the above application, please amend this application by cancelling claims 26-33 without prejudice or disclaimer.

## **REMARKS**

In the Office Action, the Examiner held claims 26-33 withdrawn from consideration as directed to a non-elected invention. The applicants are now formally cancelling these claims, without prejudice to their right to file divisional and/or continuation applications directed to these claims.

Claims 1-25 stand rejected under 35 USC 103(a) as unpatentable over Noguchi (U.S. Patent No. 6,461,901) in view of the Derwent Abstract of Japanese Patent No. 63-084089, hereinafter for convenience simply referred to as "the Abstract". This rejection is traversed. More specifically, this rejection is traversed on the grounds that it would not be apparent to one of ordinary skill in the art of fabrication of thin film transistors whether the polyimide/metal substrate provided by the Abstract would be usable in the process of Noguchi.